

EAST Search History**EAST Search History (Prior Art)**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S177	5740	(438/14,18,108,763).CCLS.	USPAT; USOCR	OR	OFF	2011/09/26 01:10
S178	1104	S177 and (sputtering or ion adj milling)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/09/26 01:10
S179	250	S178 and (semiconductor and cleaning)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/09/26 01:10
S180	156	S179 and @ad<"20040225"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/09/26 01:10
S181	65	S180 and (argon or Ar or helium or He or neon or Ne)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/09/26 01:10
S182	5740	(438/14,18,108,763).CCLS.	USPAT; USOCR	OR	OFF	2011/09/26 01:11
S183	1104	S182 and (sputtering or ion adj milling)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/09/26 01:11
S184	250	S183 and (semiconductor and cleaning)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/09/26 01:11
S185	1916	(semiconductor with (wafer or substrate) with (test\$3 or prob\$3)) and ((ion milling) or (sputter\$3 with etch\$3))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/09/26 01:11
S186	1091	S185 and @ad<"20040225"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2011/09/26 01:11
S187	157	S186 and (((ion milling) or (sputter etch\$3)) and (testing or probing or test or probe\$1) with wafer)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2011/09/26 01:11

EAST Search History (Interference)

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9/ 26/ 2011 2:41:03 AM

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bumps made of gold and its cleaning using ion milling before probing.wsp**